

THERMAL PROCESSING SYSTEM FOR IMPRINT LITHOGRAPHY

ABSTRACT OF THE DISCLOSURE

[0035] The present invention is a system that selectively directs radiation of multiple wavelengths at a substrate to facilitate pattern formation. The system may include a wavelength discriminator to filter the radiation and an absorption layer to develop a localized heat source. The localized heat source may be employed to raise a temperature of an imprinting layer. This improves the flow rate and the fill factor of the material disposed within the imprinting layer, thus reducing the time required to fill the features defined on a mold.